



Materials issues for cryogenic interferometric detectors

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- Gravitational Exchange Meeting -

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Overview

- Introduction
- Thermal noise issues
 - Thermal noise in GW detectors
 - Important material properties for thermal noise estimates
- Optical properties of silicon as a candidate material for the Einstein Telescope
- Conclusions and Summary



Introduction

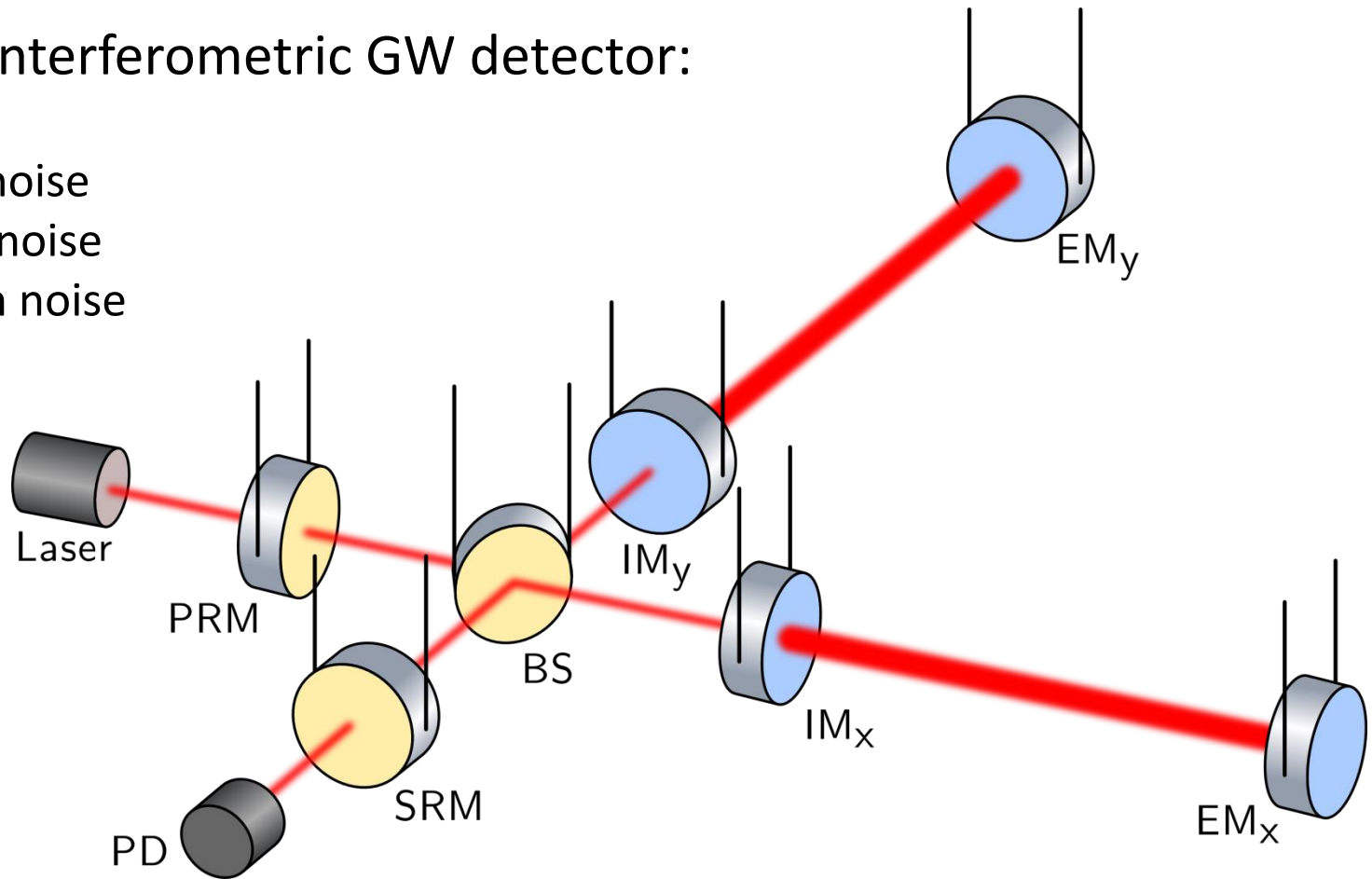
- GW detectors are amongst the most sensitive instruments ever built.
- most limitations: intrinsic noise sources
- technical noise minimized as good as possible
- noise limitations due to:
 - seismic noise
 - thermal noise
 - quantum noise



Noise in interferometric GWDs

simplified interferometric GW detector:

seismic noise
thermal noise
quantum noise





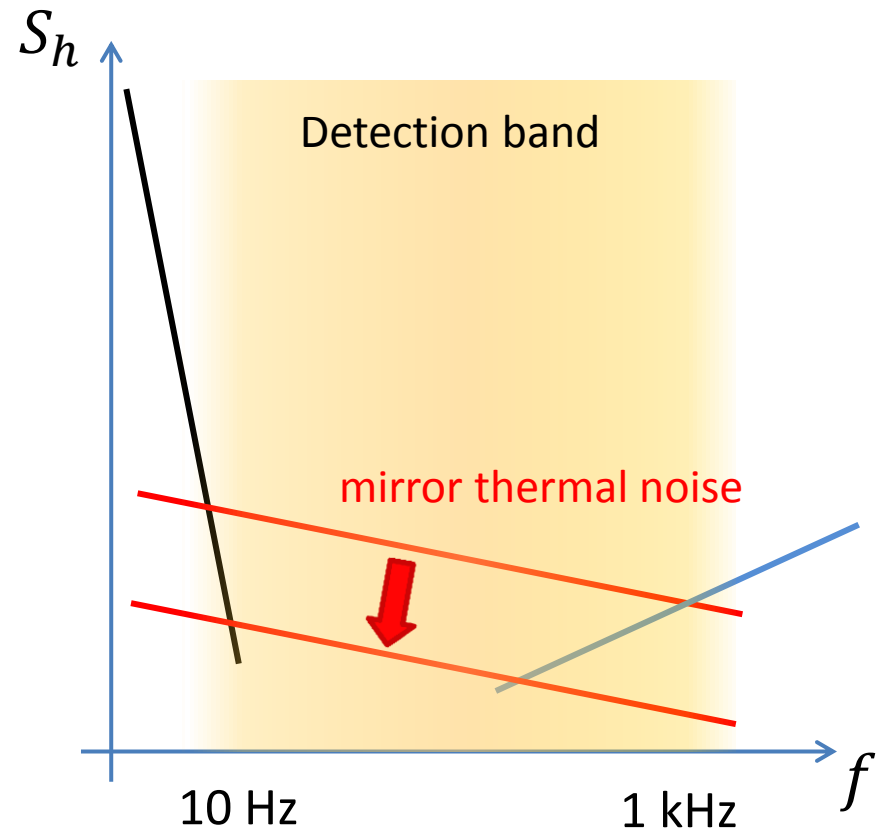
Introduction

- limits of GW detectors
- use of cryogenic temperatures to overcome thermal noise issues
- no feeling for temperature regime → investigations of materials needed as new physics has to be explored
- main issues:
 - thermal noise
 - optical properties (mainly absorption)



Thermal noise in GW detectors

- thermal noise of optical components is a limiting factor at the most sensitive part (together with quantum noise)
 - thermal noise of the suspension elements limits the low temperature performance of the detector together with quantum noise
- > 2 aims: reduction + understanding the sources of noise





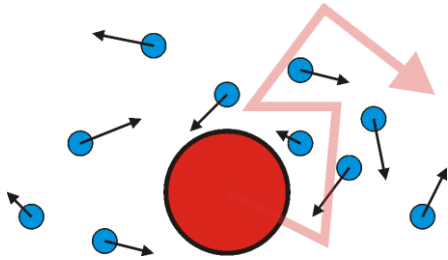
Thermal noise issues

- What is thermal noise for us?
 - „Thermal noise“ throughout this talk does not mean the whole thermal noise of the optics but the part that is seen by the laser beam.
- types of thermal noise
 - triggered by thermal energy $k_B T$
 - triggered by temperature fluctuations δT that couple via temperature dependence of material properties



Thermal noise issues

- Thermal energy triggered noise – Brownian thermal noise



VIDEO
(not included in online version)

- size too large-



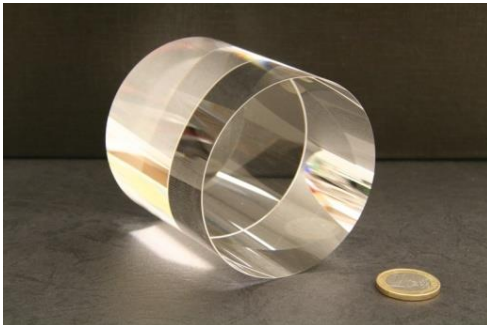
Thermal noise issues

- Thermal energy triggered noise – Brownian thermal noise
- example: thermal noise of a mirror substrate

$$S_X^2(f, T) = \frac{2k_B T}{\pi^{3/2} f} \times \frac{1 - \sigma^2}{w Y} \times \phi_{substrate}(f, T)$$

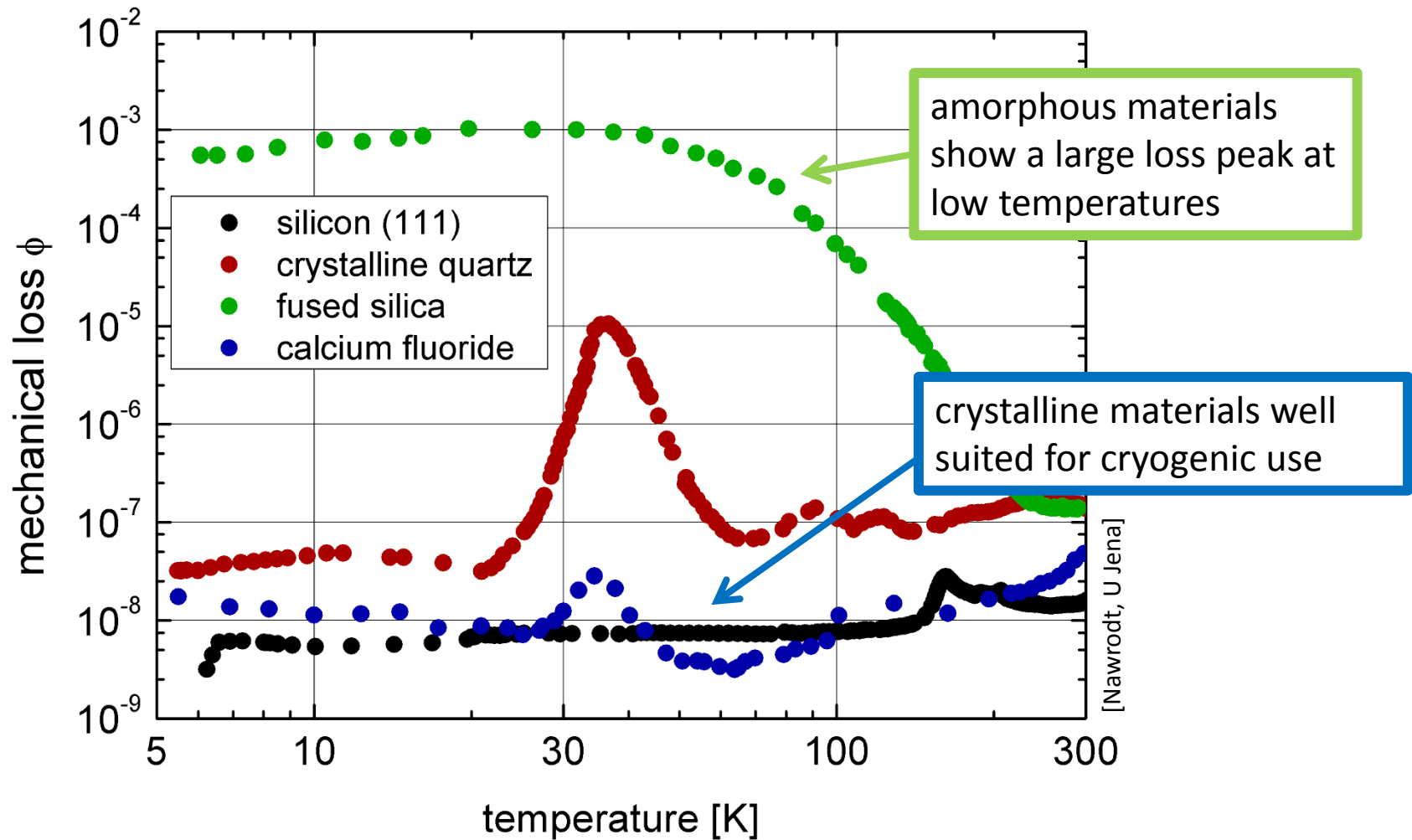
[Liu, Thorne 2000]

- lower temperature T
- increase beam diameter w
- decrease mechanical loss ϕ





Thermal noise issues





Thermal noise issues

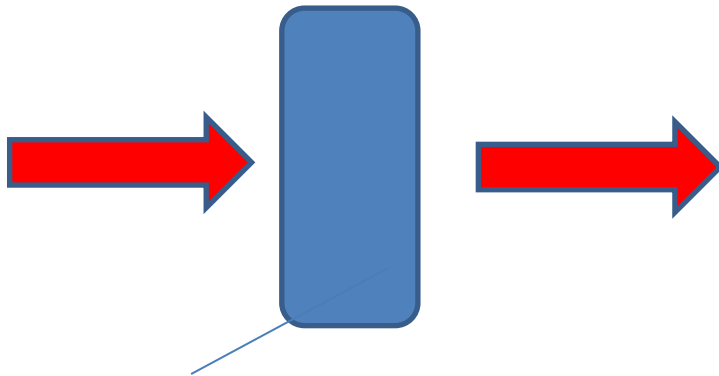
- Temperature fluctuation triggered thermal noise
- mechanism:
 - at given temperature T fluctuation always δT
 - material properties influence read out of laser beam (e.g. coefficient of thermal expansion determines position of surface, refractive index determines phase of transmitted light)
 - Fluctuations of temperature couple directly into the phase read out
= noise



Thermal noise issues

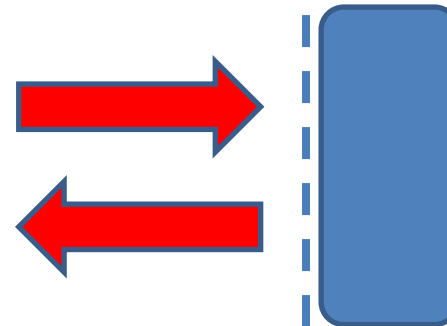
- Temperature fluctuation triggered thermal noise
- example:

transmissive optics
(e.g. ITM)



refractive index is temperature
dependent (dn/dT)

reflective optics



CTE determines front face



Thermal noise issues

- in both case – cryogenic operation
 - reduction of thermal energy
 - reduction of „coupling coefficients“ by means of 3rd law of thermodynamics

„All temperature dependent parameters become constant towards $T = 0$ K.“
- However: high laser power desired for reduction of quantum noise
→ optimization process needed



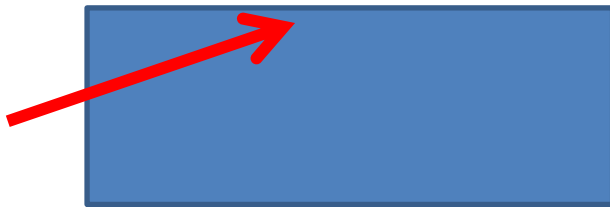
Thermal noise issues

- unknown parameters?
 - thermal parameters
 - mechanical parameters
 - optical parameters
- measurement of these parameters needed
 - thermal conductivity (collaboration with KAGRA people)
 - Q-factor measurements for mechanical loss spectroscopy
 - dn/dT measurement
 - ...



Thermal conductivity of Sapphire fibers

- Heat extraction is crucial for cryogenic operation.
- KAGRA uses sapphire fibers to remove heat from the mirrors.
- example: check of influence of surface quality



rough surface:
phonon gets scattered at surface



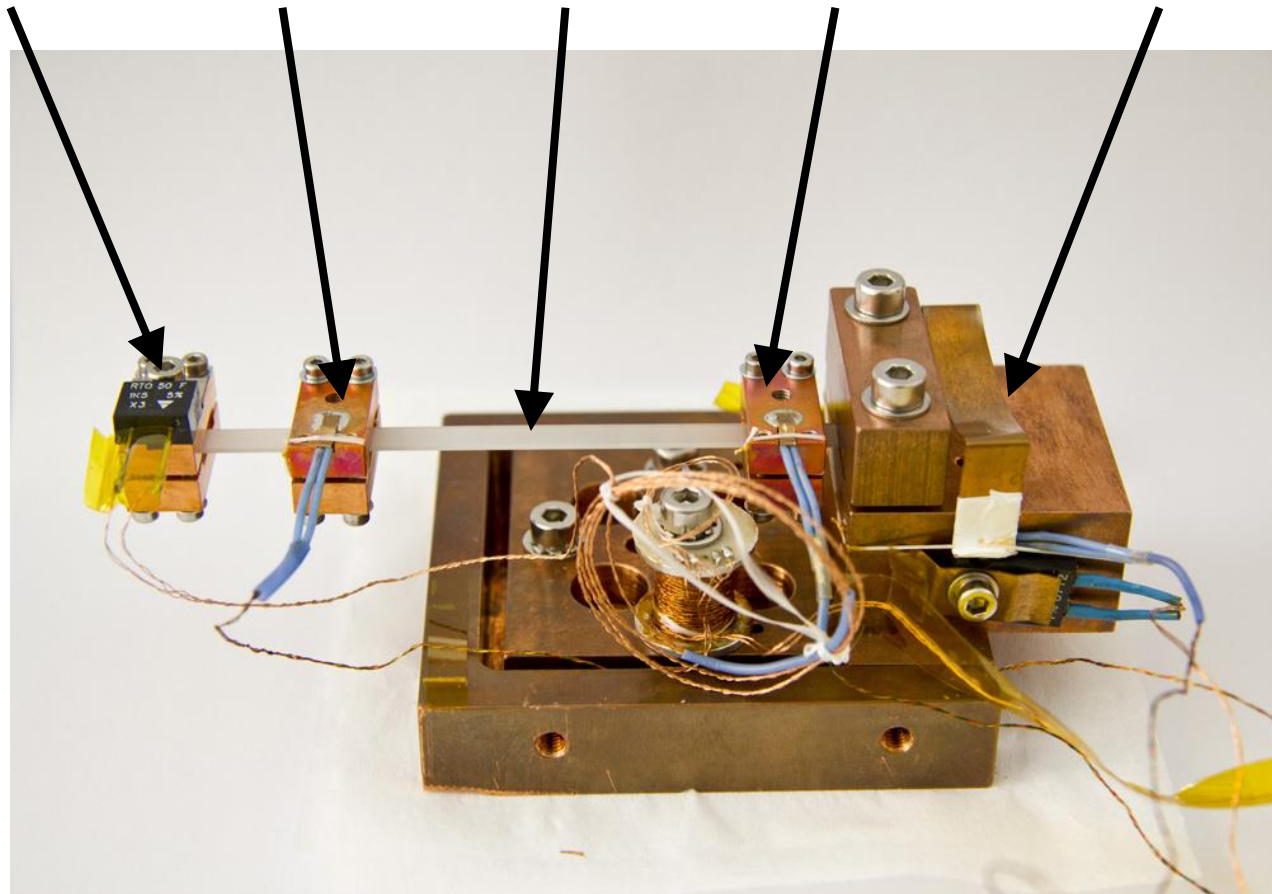
polished surface:
phonon gets reflected at surface

- investigation in collaboration with Nikhef (surface quality) and ICRR (test of nailhead fibres)



Thermal conductivity of Sapphire fibers

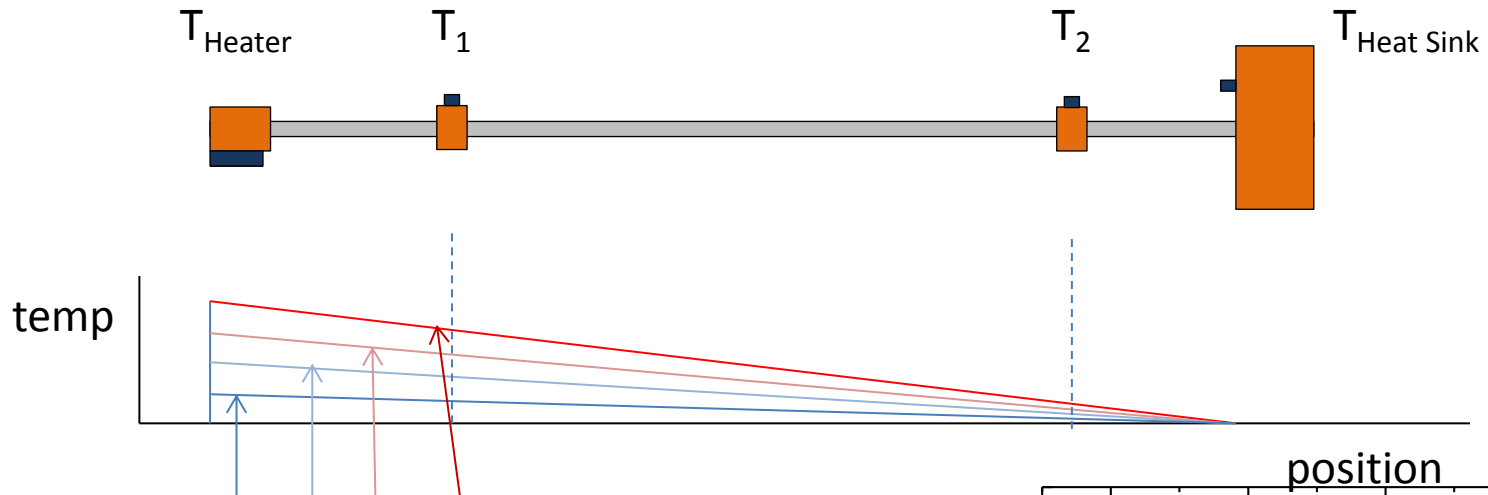
Sample Heater Temperature Sensor 1 Sample Temperature Sensor 2 Temperature Controlled Heat Sink



[credits to G. Hofmann, C. Schwarz]



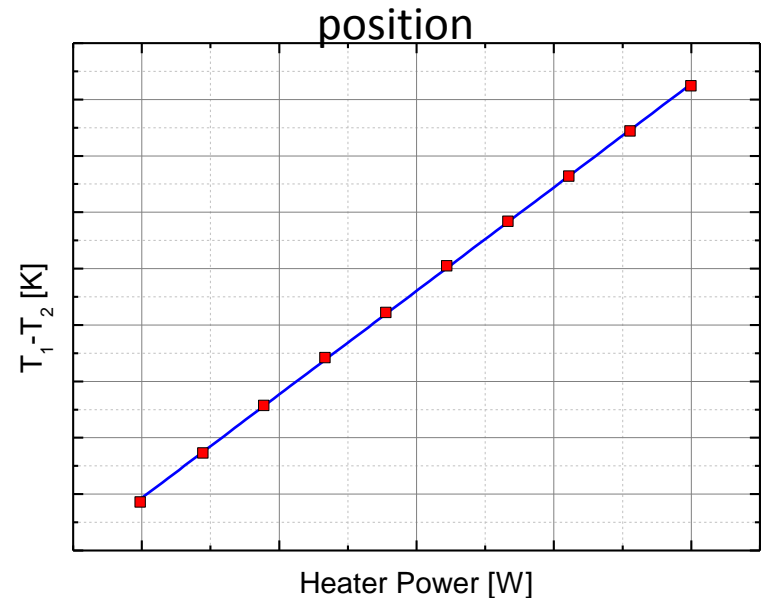
Thermal conductivity of Sapphire fibers



$$P_1 < P_2 < P_3 < P_4$$

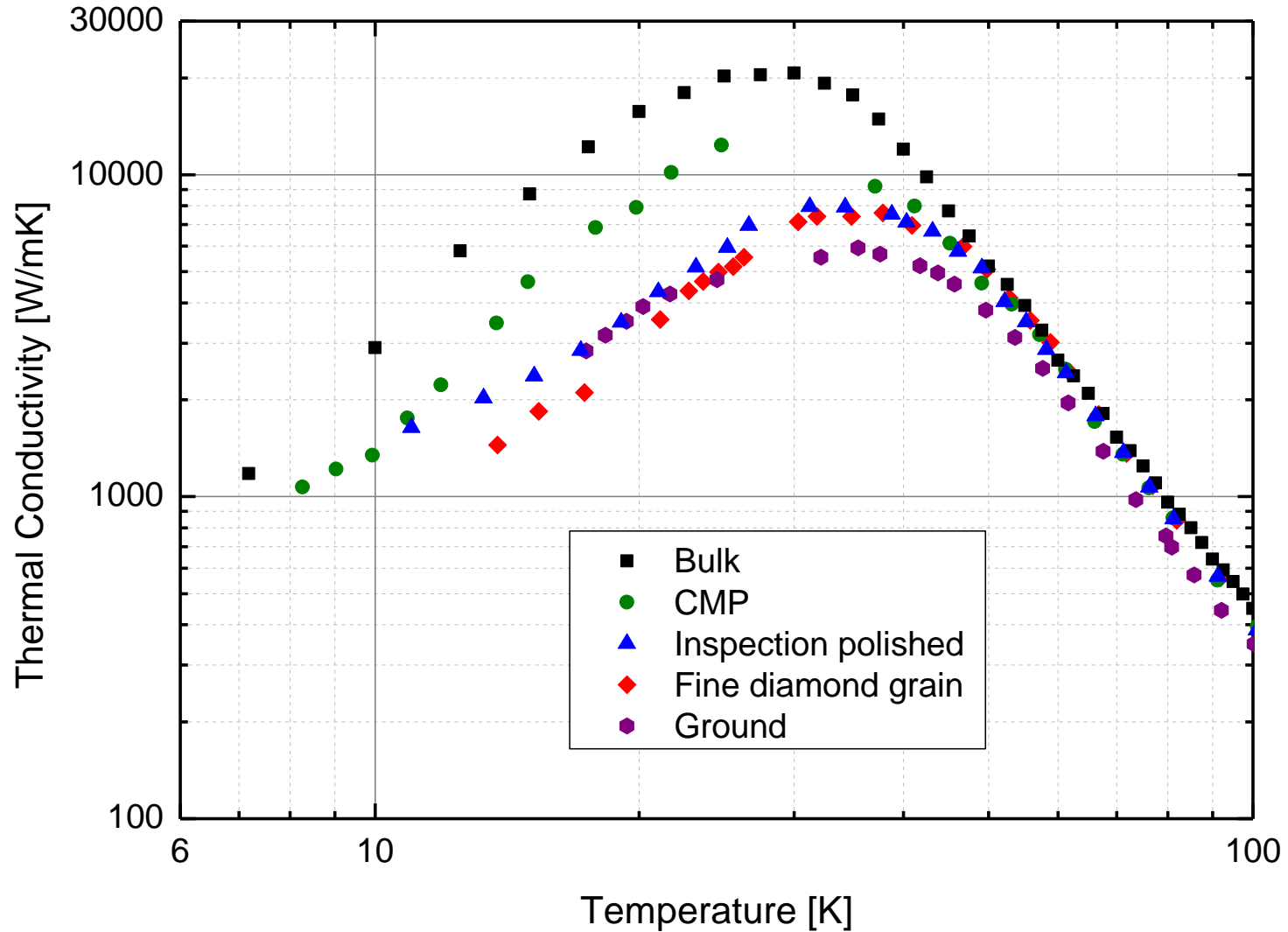
$$\Delta T = T_1 - T_2$$

$$\Delta T_1 < \Delta T_2 < \Delta T_3 < \Delta T_4$$





Thermal conductivity of Sapphire elements





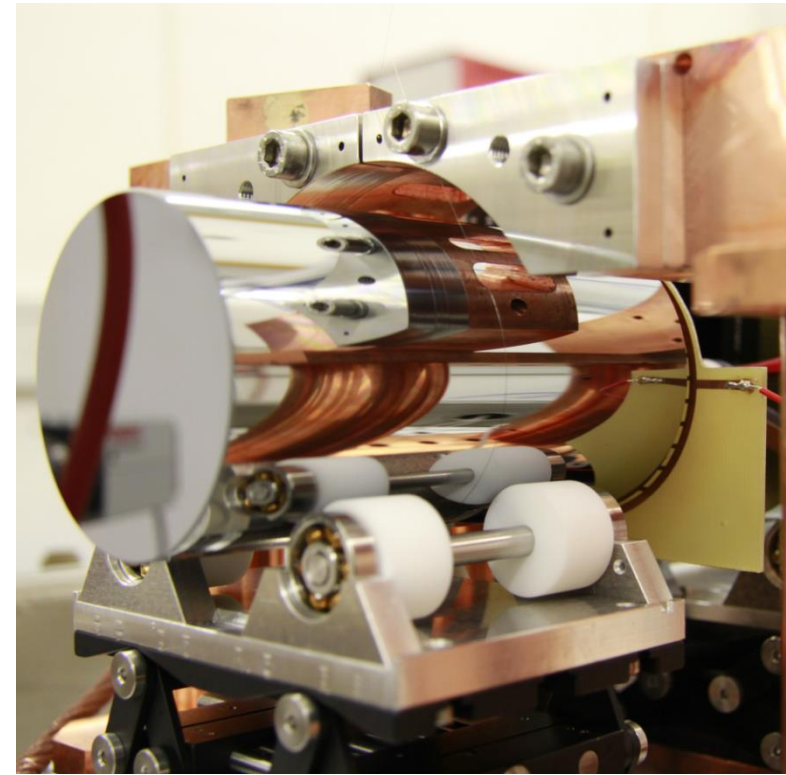
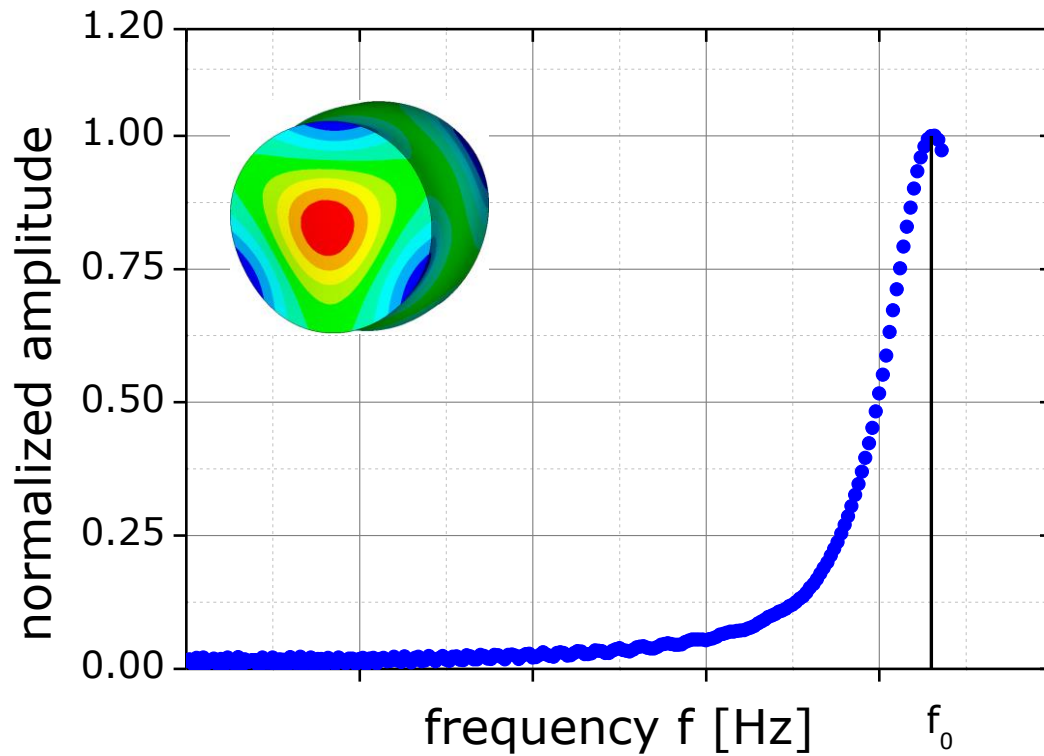
Mechanical loss spectroscopy

- mechanical loss is important parameter for thermal noise estimates, also gives insight into the solid state physics of the sample
- cryogenic mechanical spectroscopy is used to study this parameter



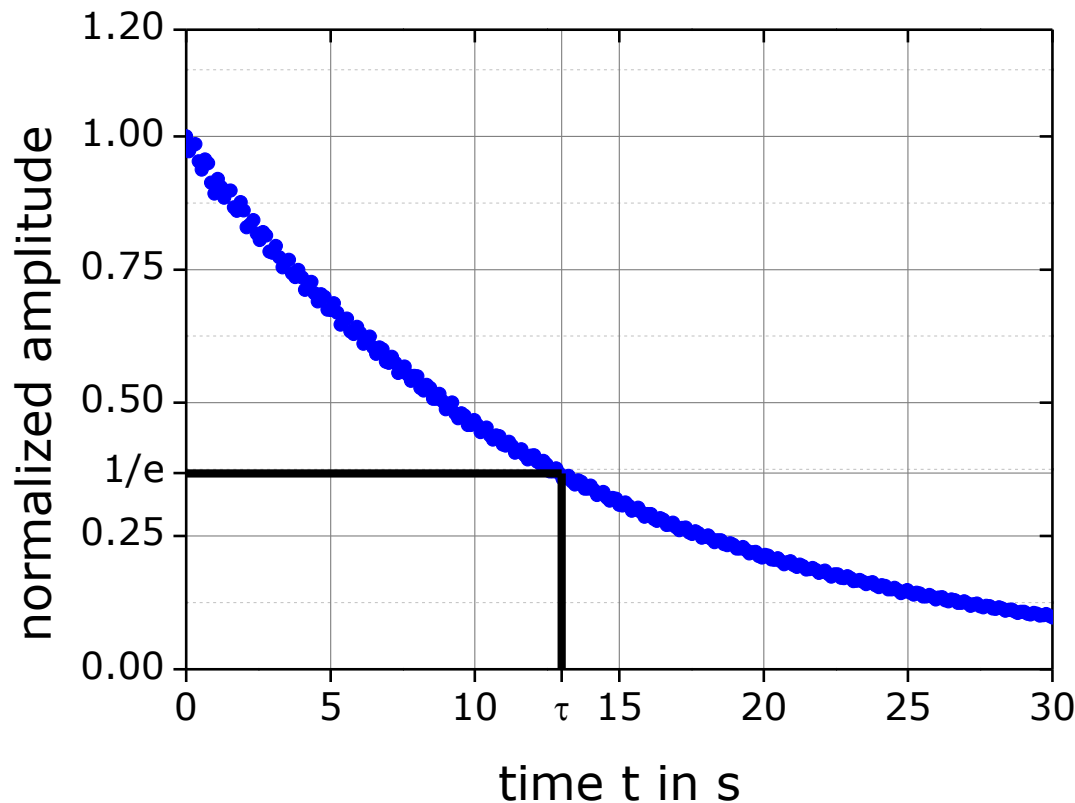


Mechanical loss spectroscopy





Mechanical loss spectroscopy



Freely decaying ring down
of the oscillation at f_0 :

$$x(t) = x_0 \exp\left(\frac{-t}{\tau}\right) \cos \omega_0 t$$

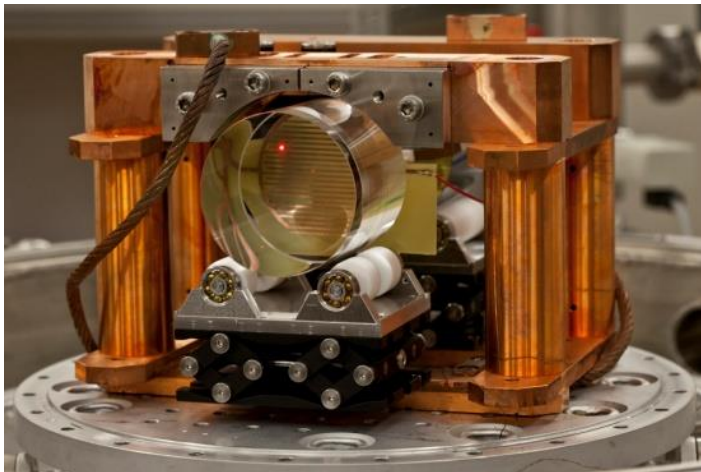
Ratio of dissipated to
stored energy per cycle
yields the mechanical loss:

$$\phi = \frac{\Delta E}{2\pi E} = \frac{1}{\pi f \tau}$$

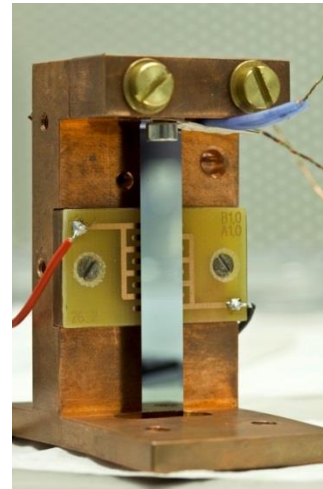


Mechanical loss spectroscopy

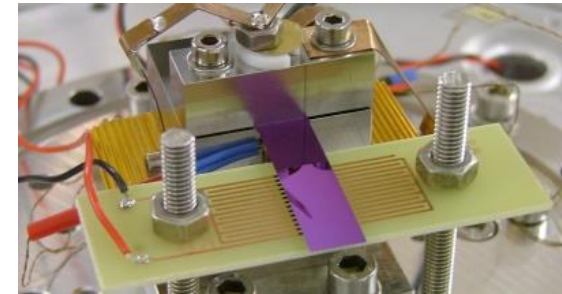
- Aim: measuring *intrinsic* loss → avoid external dissipation → sophisticated setups are needed



thin wire suspension
for bulk materials



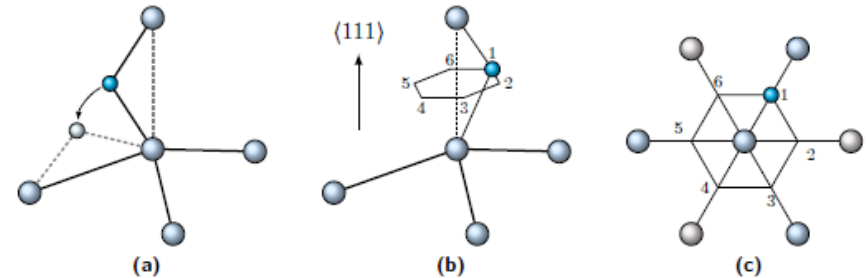
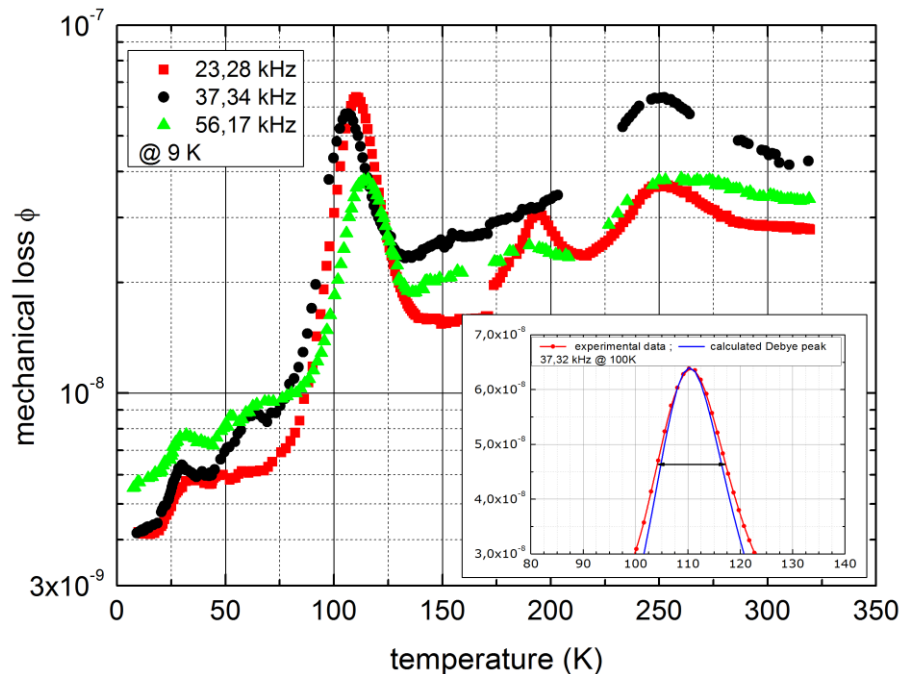
thin silicon blades
used for coating and surface
investigations





Mechanical loss spectroscopy

- f_0 and T are changed to obtain a mechanical loss spectrum



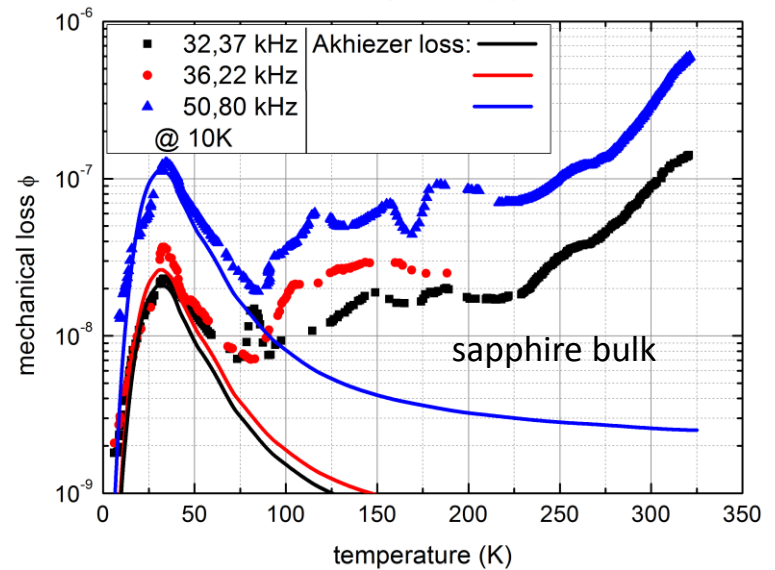
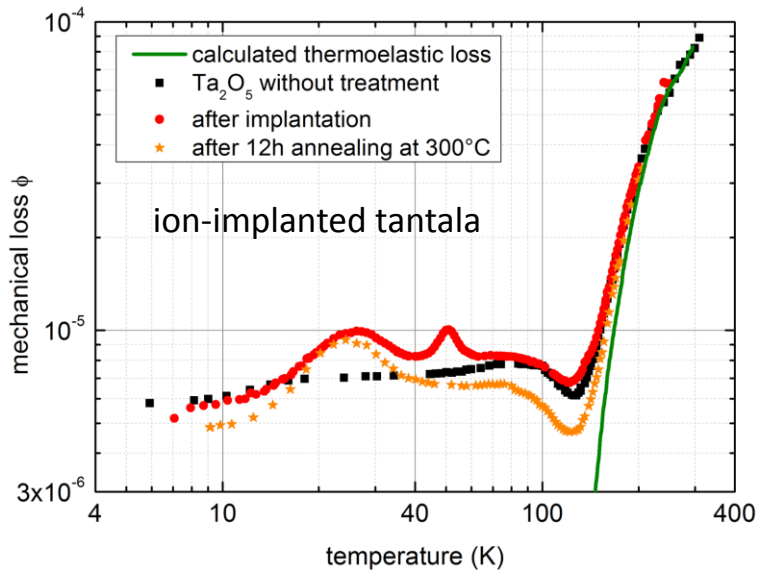
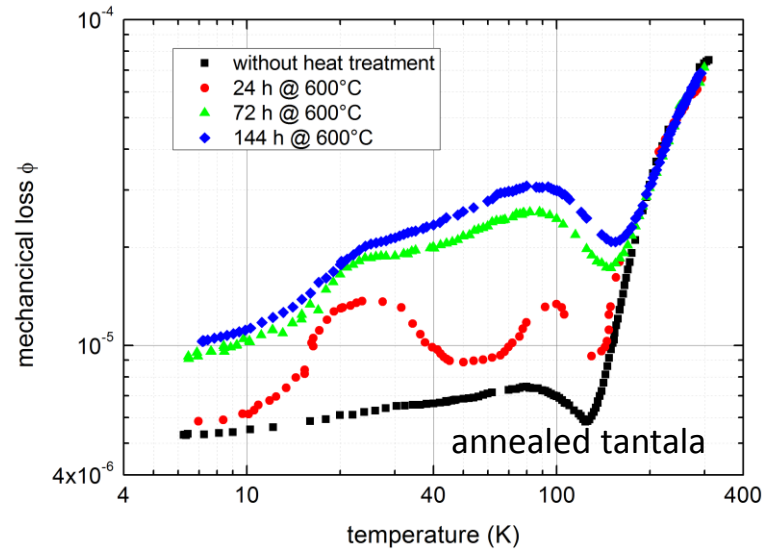
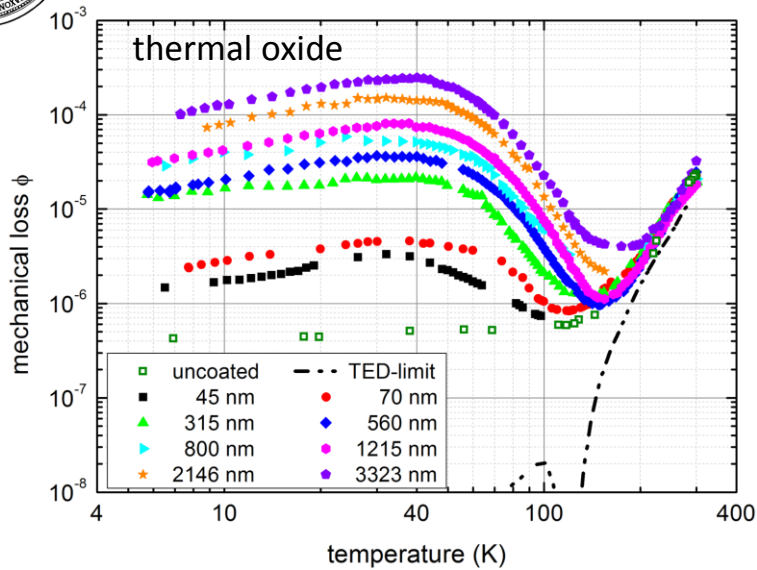
oxygen changes positions within the Si
 → relaxation → damping at 125 K

[Schwarz et al. SSP 184 (2012)]

- collaboration with IGR at Glasgow
- aim: understanding the origin of the loss to avoid it



Mechanical loss spectroscopy





Mechanical loss spectroscopy

- Questions that can be answered with this technique:
 - optimum operational temperature
 - active or inactive impurities
 - methods to lower the mechanical loss

 - evaluation of the Brownian thermal noise without need to directly measure it



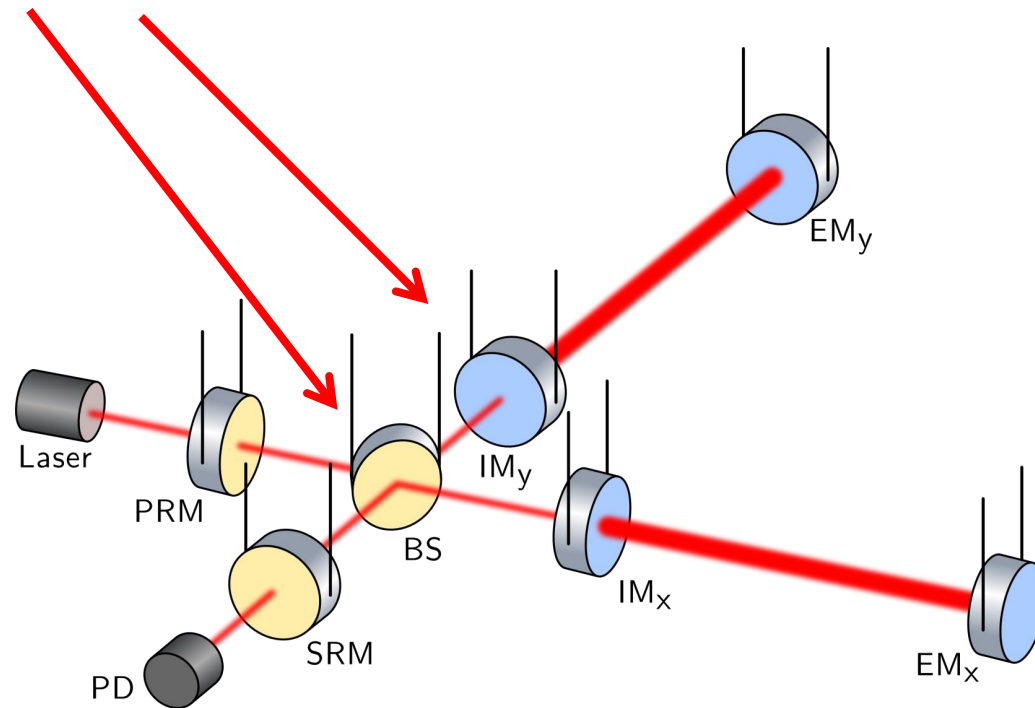
Silicon as a baseline material for ET-LF

- low mechanical loss
- high thermal conductivity
- good mechanical stability
- many existing techniques (growing, polishing, cutting) due to semiconductor industry
- available in large size and high quality (up to 450 mm diameter)
- however: not transparent at 1064 nm → change to 1550 nm needed → optical parameters need to be investigated



Thermo-refractive noise in GW detectors

- Temperature fluctuations cause the refractive index to fluctuate as well → how much, especially at low temperatures?
- possible optics: BS, ITM



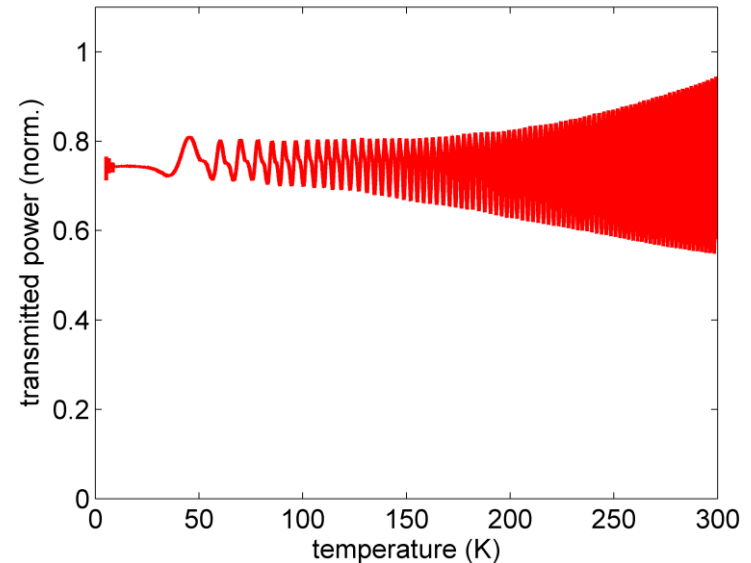


Thermo-refractive coefficient of silicon

- Thermo-refractive coefficient dn/dT needed at cryogenic temperatures and at 1550 nm



Investigation of transmission through a parallel sample during cooling

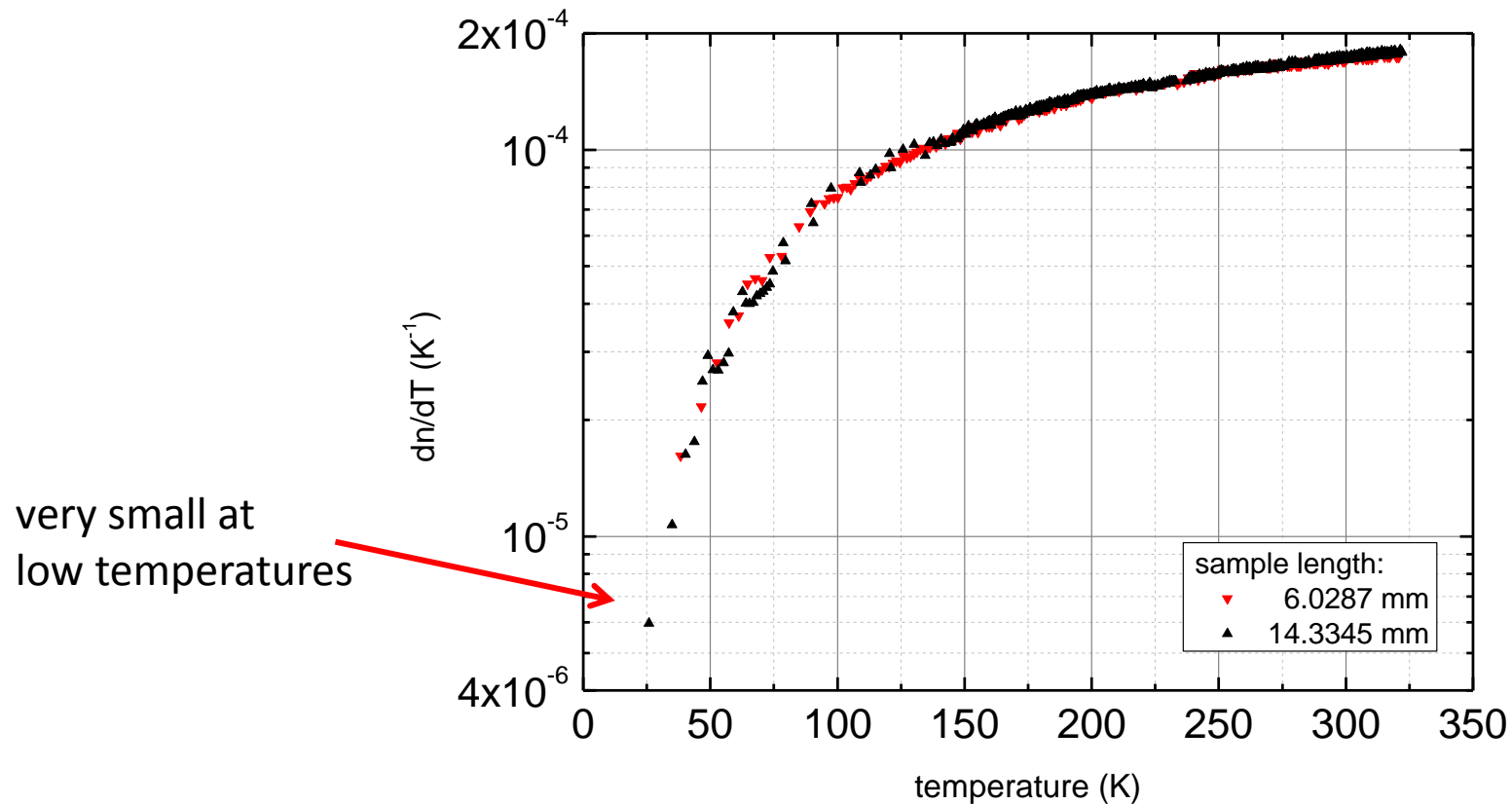


fringes contain both CTE and dn/dT



Thermo-refractive coefficient of silicon

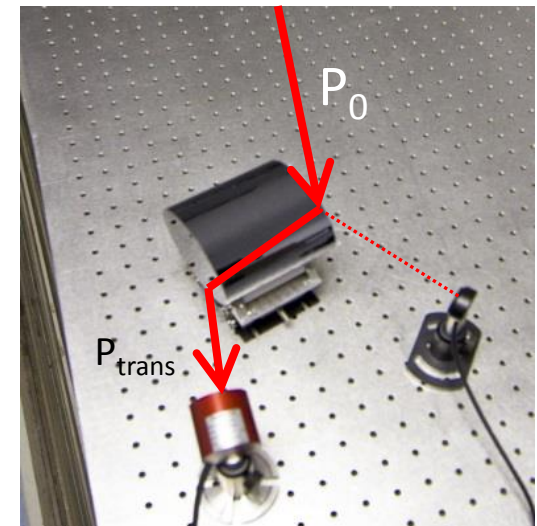
- Extraction of dn/dT reveals its temperature dependence





Optical absorption of silicon

- Cryogenic operation needed for crystalline materials
 - high thermal conductivity of suspension elements needed (seen before)
 - low optical absorption needed in transmissive components





Optical absorption of silicon

- band structure of semiconductors

single atoms



atoms in a solid



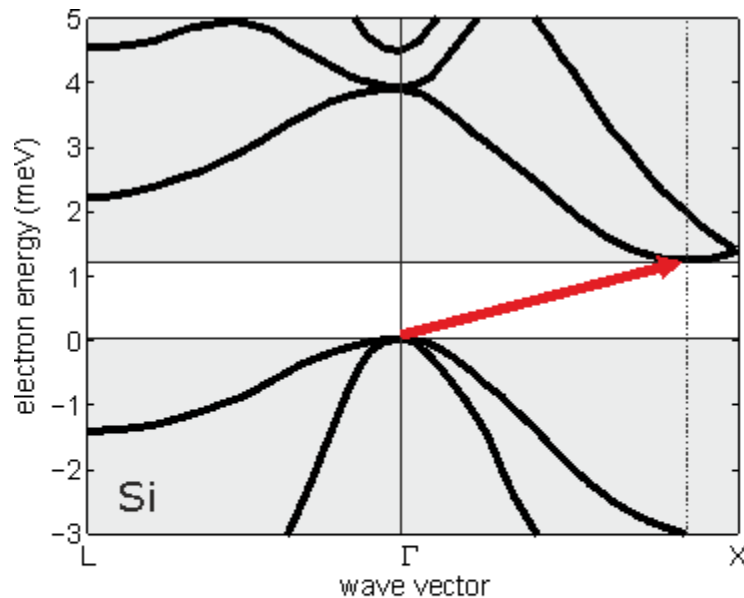
discrete energy levels with forbidden gaps in between

energy levels split (Pauli principle), formation of bands

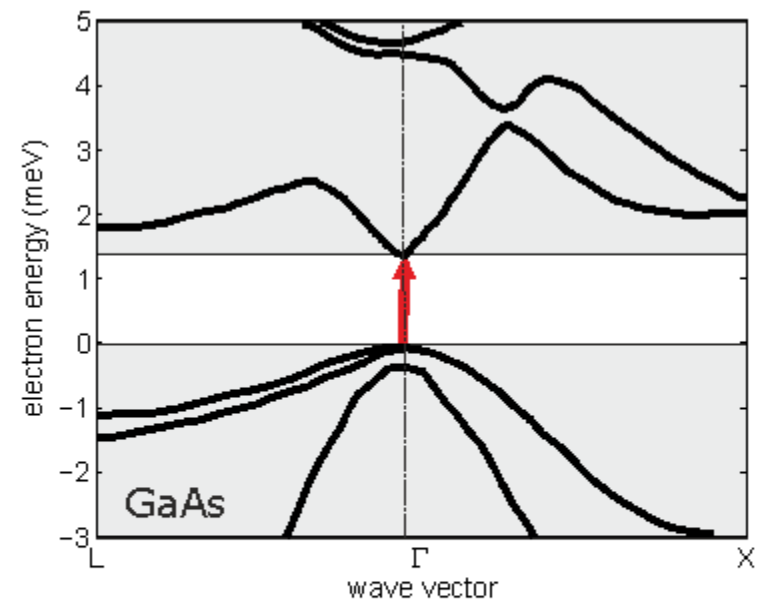


Optical absorption of silicon

- band structure of semiconductors – direct and indirect transitions



Electronical band structure of silicon. The maximum of the valence band occurs at the Γ point, whereas the minimum of the conduction band is located at $0.8 X$. Indirect transitions from the valence band to the conduction band are only possible if $\Delta k \neq 0$ and if the energy of the photon is larger than 1.12 eV (gap energy).

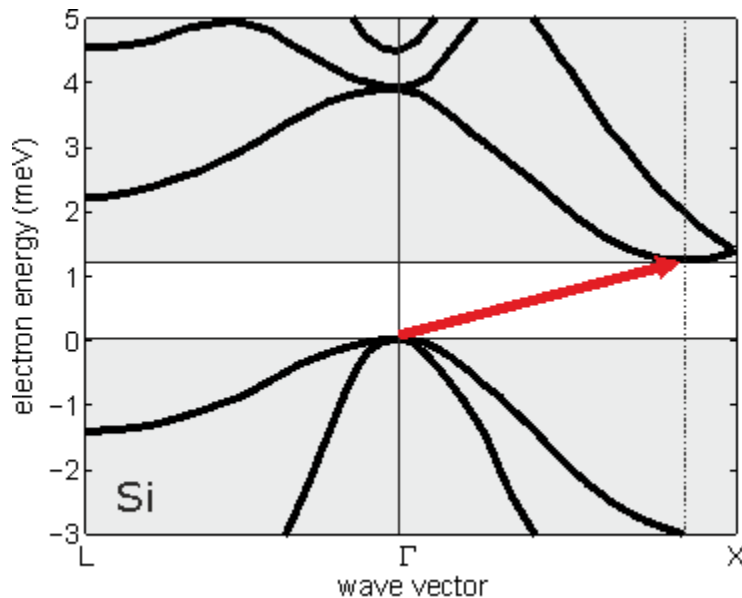


Electronical band structure of gallium arsenide. The maximum of the valence band occurs at the Γ point as well as the minimum of the conduction band. Direct transitions from the valence band to the conduction band demand $\Delta k = 0$ and are possible as soon as the photon energy is larger than 1.42 eV (gap energy).

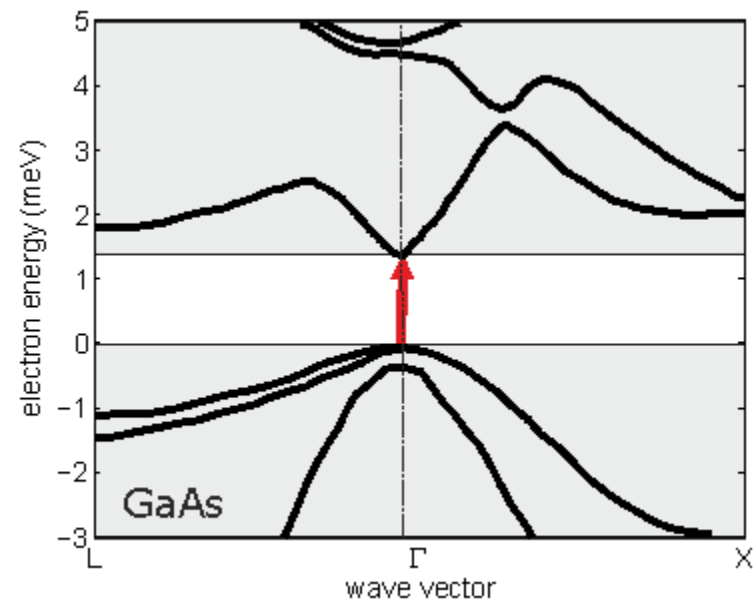


Optical absorption of silicon

- band structure of semiconductors – direct and indirect transitions



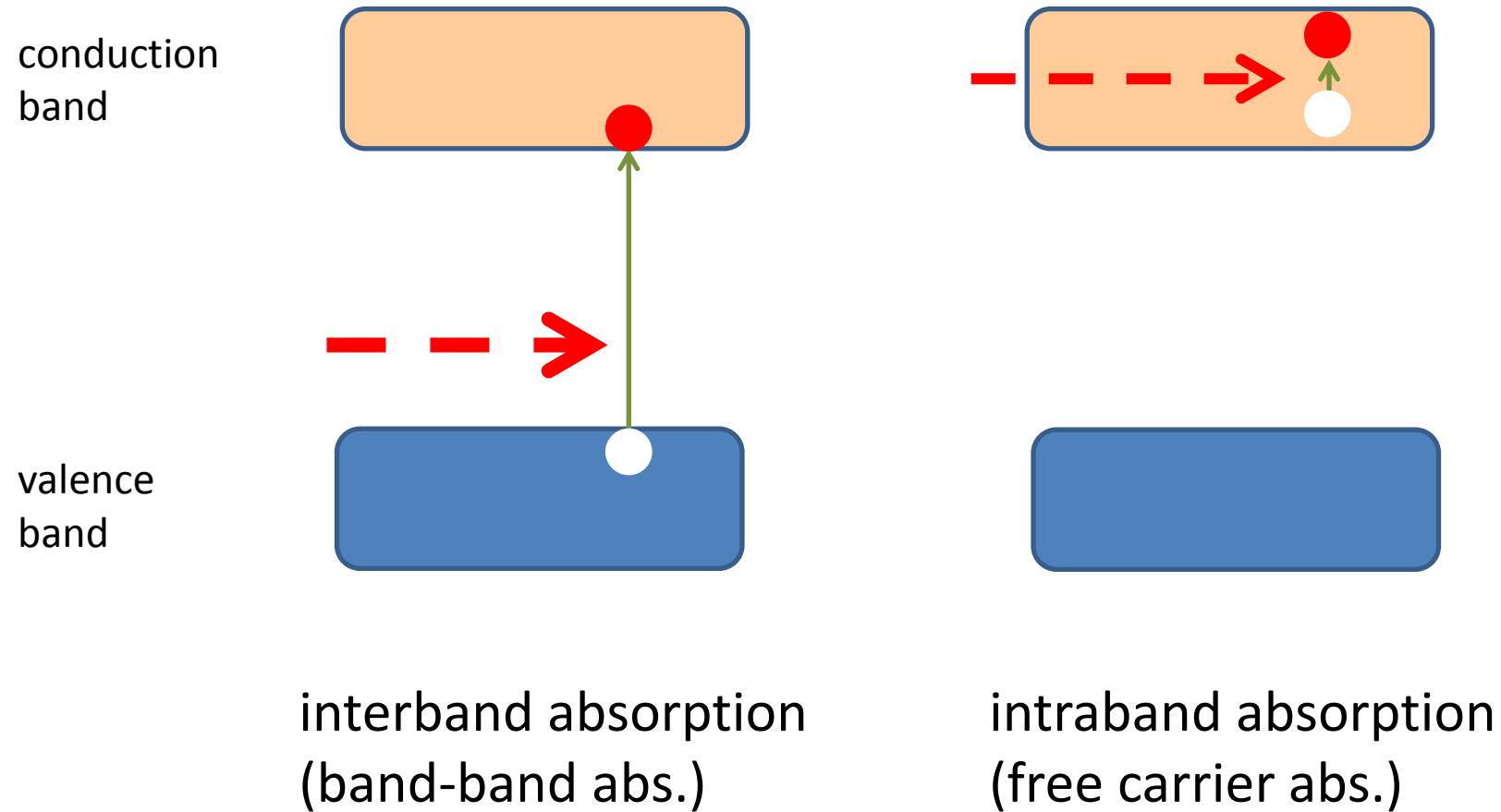
transition probability low
(3 particles involved)



transition probability high
(only 2 particles involved)



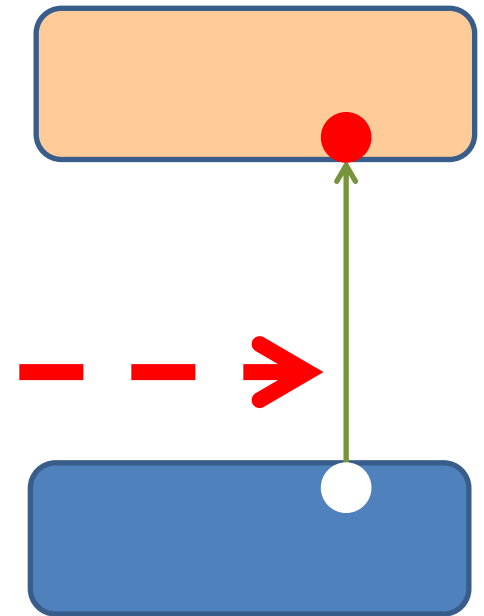
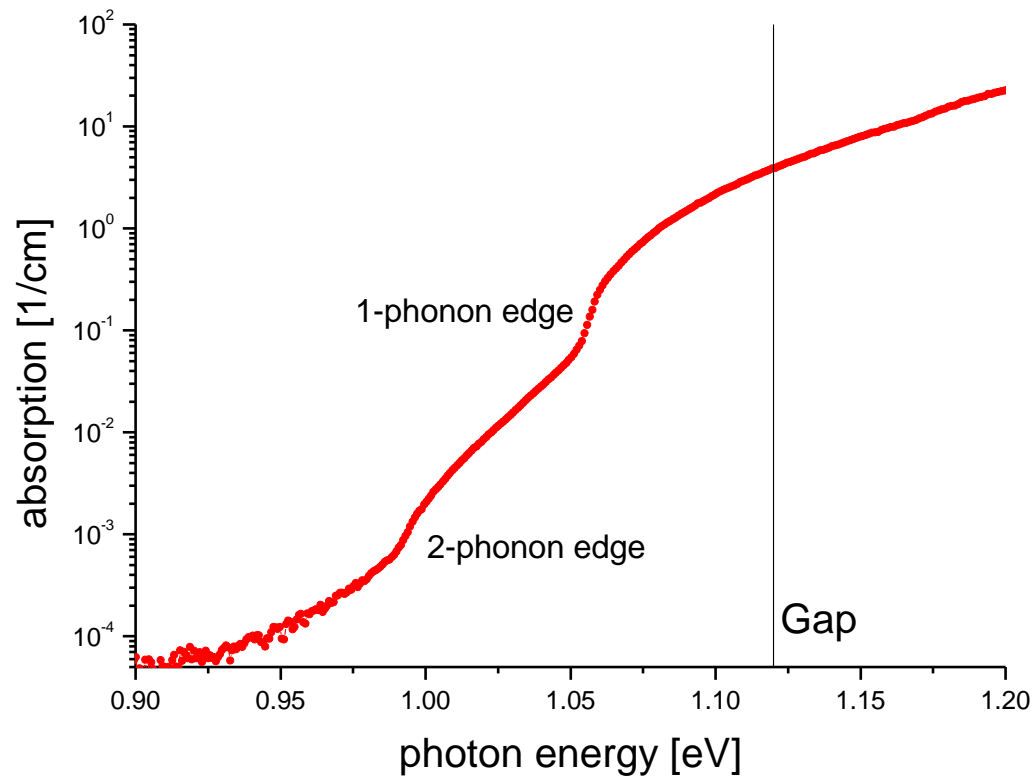
Optical absorption of silicon





Optical absorption of silicon

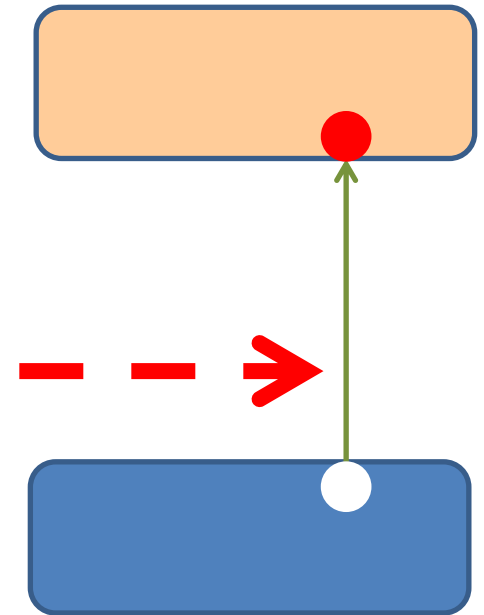
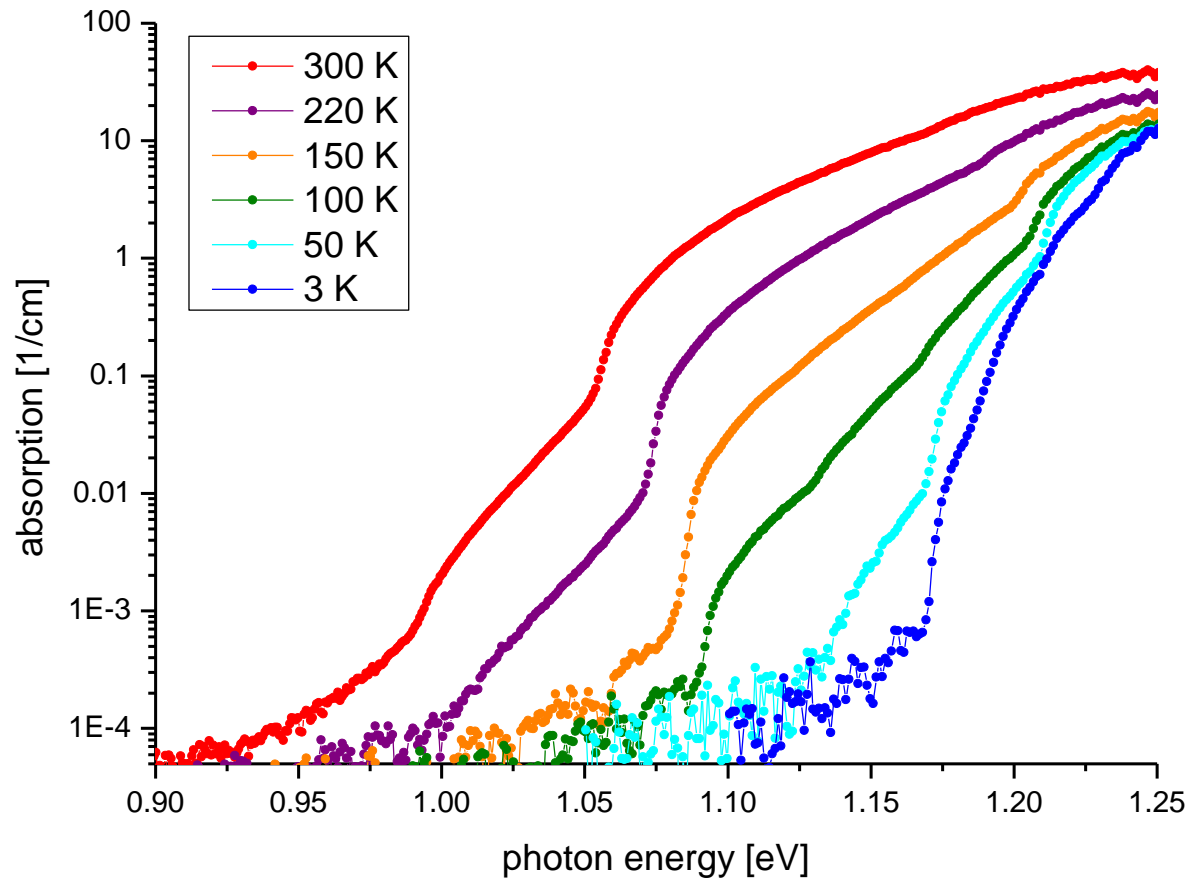
- Band-band-absorption





Optical absorption of silicon

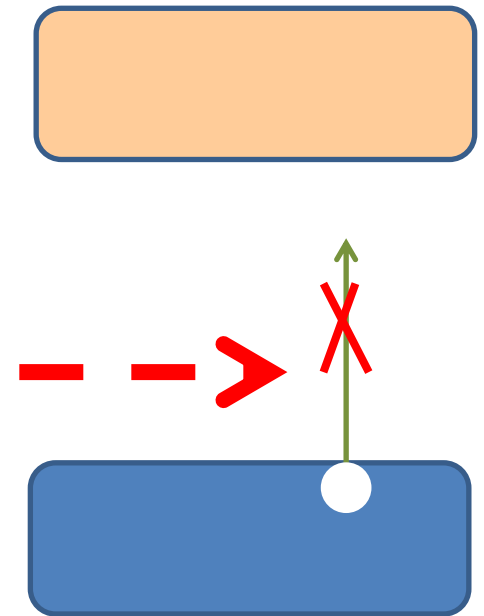
- Band-band-absorption





Optical absorption of silicon

- Band-band-absorption
 - Photon energy has to be near the gap energy
 - Phonon assisted absorption is temperature dependent.
- use of light beyond the gap (e.g. 1550 nm)

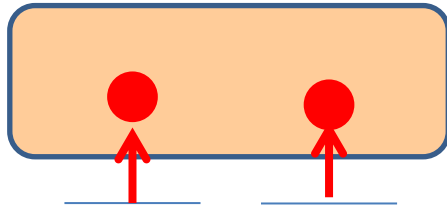




Optical absorption of silicon

- Free carrier absorption

– origin of carriers



typ. 45 meV

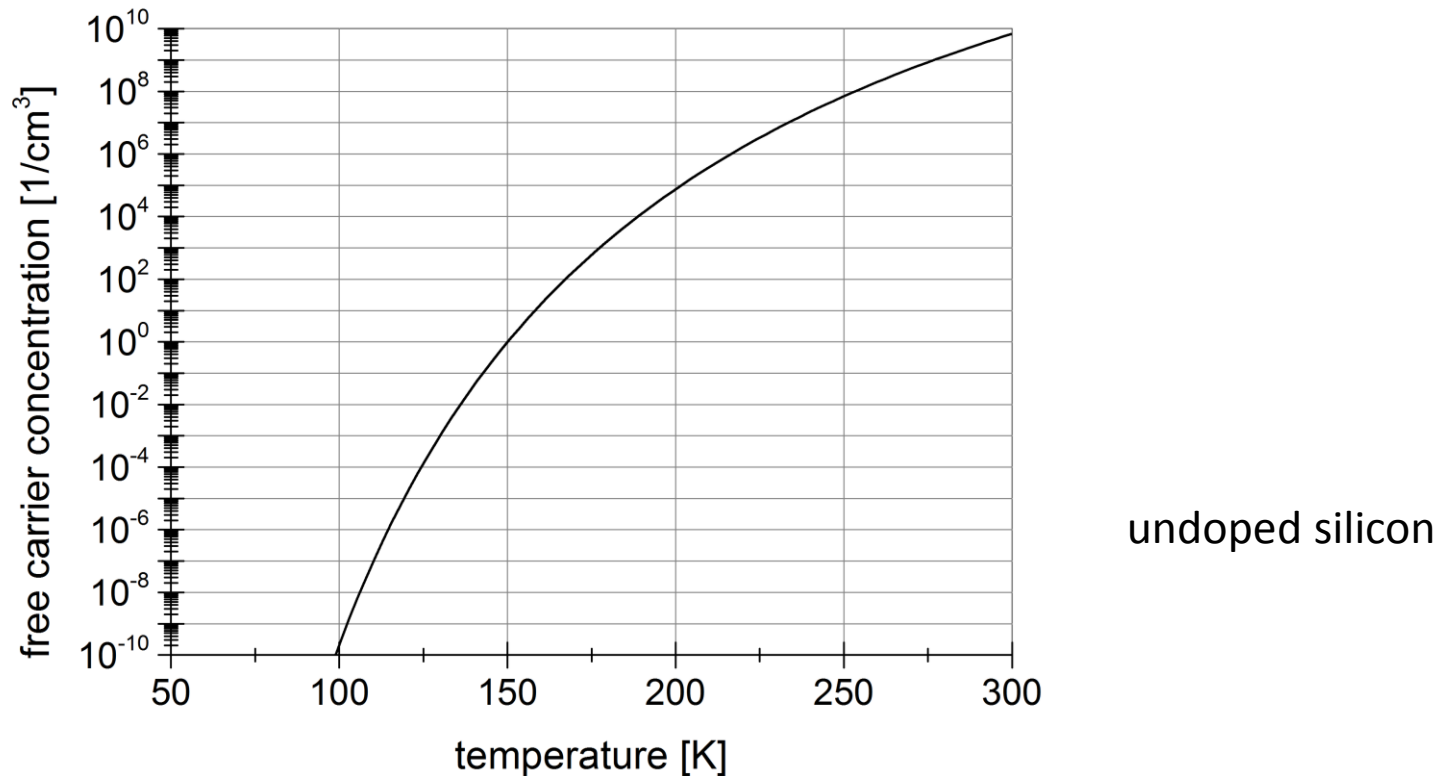
Free carriers are released from doping states. Necessary energy is taken from thermal bath.





Optical absorption of silicon

- Free carrier concentration as function of temperature

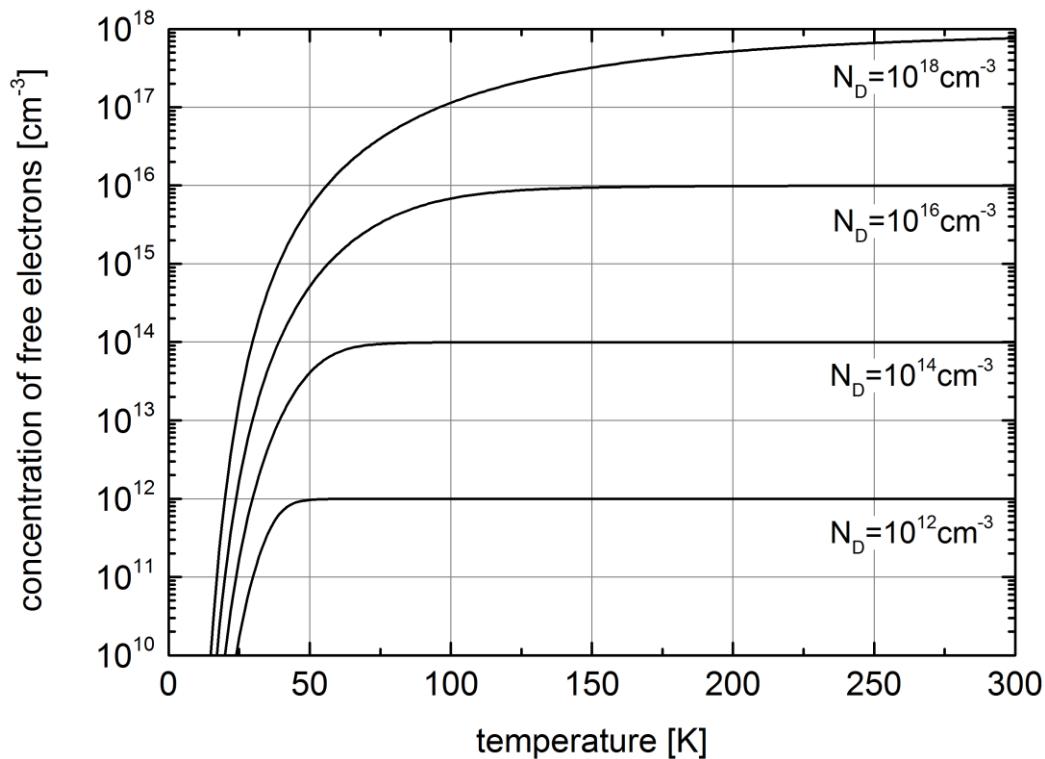


- Free carrier concentration drops very rapidly (1/cm³ at 150 K)



Optical absorption of silicon

- Free carrier concentration as function of temperature



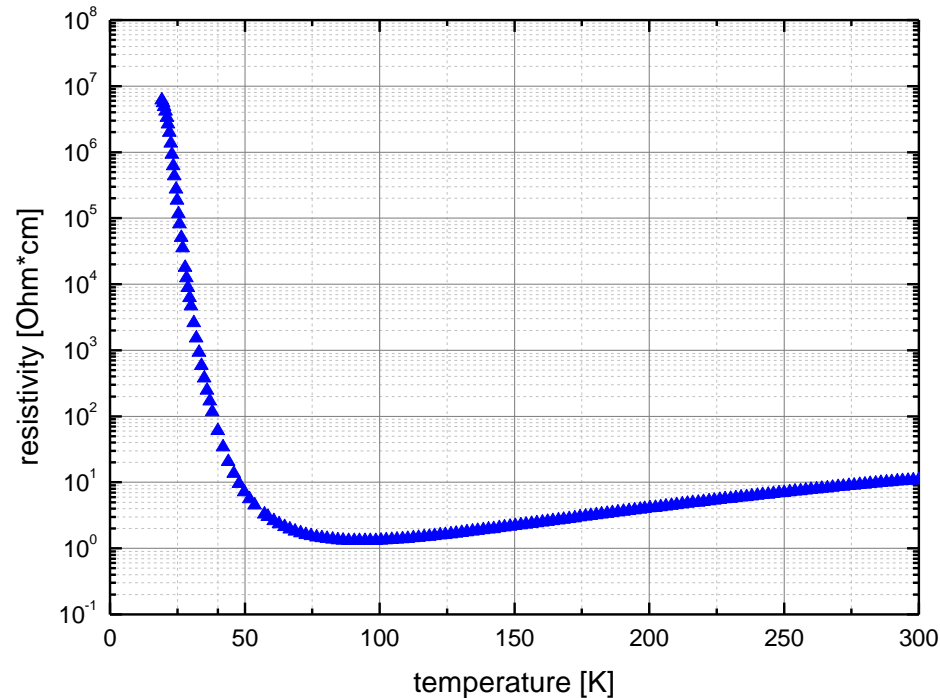
doped silicon
 N_D – doping concentration

- Very low temperatures needed (below 50 K) to get rid of FCA!



Optical absorption of silicon

- freeze-out of carriers can be observed electronically by means of resistivity measurements



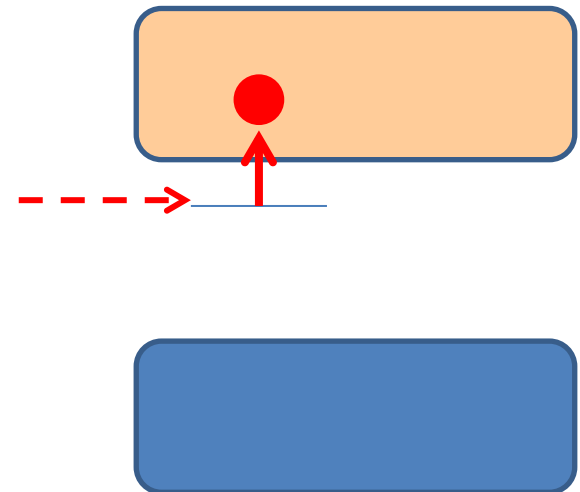
Free carriers are bound to their ground state at low temperatures.



Optical absorption of silicon

- However:

Optical absorption is observed to be nearly temperature independent but scales with concentration of doping.
- Further studies needed...
- Possible mechanism due to the optical absorption from the ground state of the dopand into the conduction band.





Optical absorption of silicon

- additional noise sources can arise from free carriers
- free carrier density influences the refractive index
 - fluctuating carrier density (thermal, via absorption, etc.) causes fluctuations of refractive index
 - refractive index change causes „carrier noise“
- further investigations are ongoing



Summary and Conclusions

- Material investigations are important for future cryogenic GW detectors due to the unknown parameters.
- Silicon and sapphire are promising candidate materials for cryogenic applications and provide suitable properties.
- Silicon as a test mass material brings free carriers into the „thermal noise game“ -> new noise sources ?